



Extending Modular Redundancy to NTV: Costs and Limits of Resiliency at Reduced Supply Voltage

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WNTC 2014 - 14 June 2014



Agenda



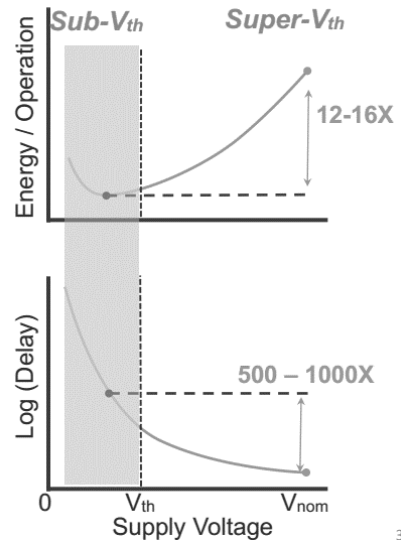
- Pros and Cons of ***Near-Threshold Computing (NTC)***
- Towards the Goal of Simultaneous Increase in ***Resilience*** and ***Energy Efficiency***
- Impact of ***Performance Variability*** for N-MR Systems
- Experimental Setup
- ***Energy Cost*** of Mitigating Variability
- Conclusions and Future Work



Increasing Interest in Near-Threshold Computing: *Limits*



- Voltage Scaling is a very effective way to reduce energy consumption
 - Total Energy = $E_{\text{dynamic}} + E_{\text{static}}$
 - Dynamic Energy directly proportional to V_{DD}^2
 - E_{static} proportional to $(V_{\text{DD}} * \text{Leakage current} * T_{\text{clk}})$
- Extreme reduction of V_{DD}
 - Sub-threshold region
 - Theoretical Lower Limit of V_{DD} is 36 mV [1]
 - >12X Energy Savings as compared to Nominal
 - Massive Performance Penalty (exponential)
 - Limited Applicability



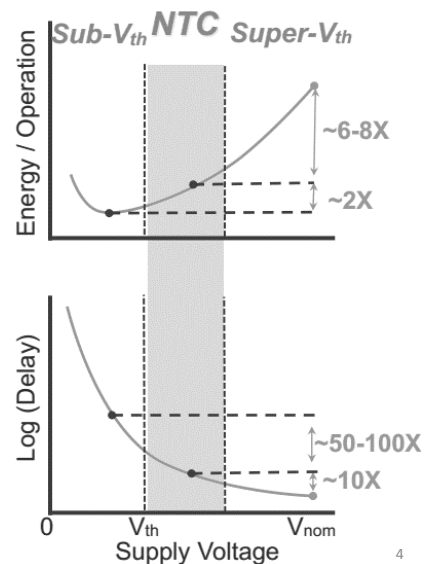
[Fick 2012] http://web.eecs.umich.edu/~mfajtik/fick_isscc2012_slides.pdf



Increasing Interest in Near-Threshold Computing: *In-Practice*



- Voltage Scaling is a very effective way to reduce energy consumption
 - Total Energy = $E_{\text{dynamic}} + E_{\text{static}}$
 - Dynamic Energy directly proportional to V_{DD}^2
 - E_{static} proportional to $(V_{\text{DD}} * \text{Leakage current} * T_{\text{clk}})$
- Optimum reduction of V_{DD}
 - Near-Threshold region
 - Lower limit of V_{DD} in commercial applications is ~70% of nominal [1]
 - Only 2X Energy Difference from Sub-Threshold
 - 10X Delay Difference from Sub-Threshold
 - Still >6X Energy Reduction as compared to Nominal



[Fick 2012] http://web.eecs.umich.edu/~mfajtik/fick_isscc2012_slides.pdf



Limitations of NTC: Soft Errors



- Soft Errors in logic datapath
 - Cause: Radiation-induced transient charge within a logic path which is ultimately latched by a F/F
 - More-than-ECC (Error Correcting Codes) needs to be done to mitigate soft errors for logic
- Soft Error Rate (SER) for logic at *NTV* is shown experimentally to be comparable to the SER for memory circuits [2]
 - Critical charge Q_{crit} needed to cause a failure decreases as V_{DD} is scaled. The SER has an exponential dependence on critical charge.
 - For 40nm and 28nm nodes, SER doubles when V_{DD} is decreased from 0.7V to 0.5V
- Soft Error masking mechanisms for logic paths
 - Logical Masking: fewer gate in critical path to regain lost throughput, less chance of the pulse being masked by logical computation of other gates in the path.
 - Electrical Masking: large pulse transients are created, as compared to supply voltage
 - Latching-window masking: lowered operating frequency has positive impacts here
- Non-planar devices offer a means to reduce SER.
 - 22nm Tri-gate technology is shown to reduce neutron and alpha particle induced SER at nominal voltage by 4-fold and 10-fold respectively compared to a 32nm planar process [3]
- Reduced pipeline depths, technology scaling, and *NTV* can be anticipated to have detrimental effects on logic SER

5



Adoption of NTC for Embedded applications



- A new direction for highly-reliable energy-efficient Embedded Processors/Chips
 - Energy-Efficiency → *NTC*
 - High-Reliability → *Spatial/Temporal Redundancy*
- Spatial Redundancy used in *mission-critical* applications for *resilience* as spare components help to tolerate failures [4],[5]
 - Harsh environments: autonomous vehicles, satellites, etc.
 - It is possible to reduce overhead by protecting only the critical components
- Temporal Redundancy (Repeated Execution) is also effective for soft error masking, however, performance loss is massive.
 - Suitable for area-constrained applications
- **Spatial:** *N-Modular Redundancy (N-MR)* and majority voting
 - System operates correctly as long as majority of the modules are functioning
 - Typically, $N=3$ is employed: referred to as TMR systems

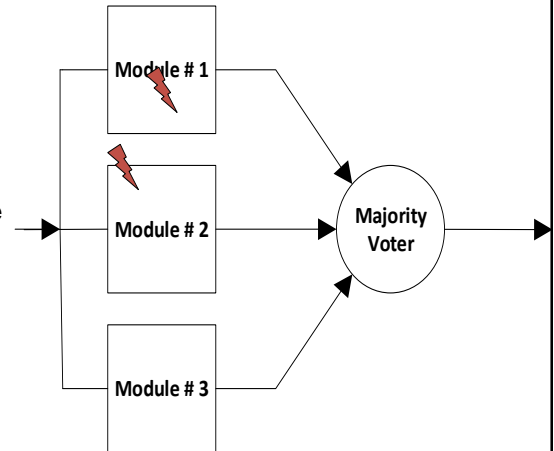
6



Soft Error Masking at NTV



- SER in logic paths can be reduced by schemes such as gate-sizing [6] and dual-domain supply voltage assignment [7]
 - Harden components which are more susceptible to soft errors. For instance, logic gates near the flip-flop
 - Difficult to provide comprehensive coverage. For instance, dual-domain voltage assignment is only able to reduce SER by 33.45%
- TMR provides comprehensive masking against soft-errors
 - Most soft-errors are mask-able or diagnosable
 - The probability of a non-diagnosable error is very low, i.e. what is the probability of majority instances producing identical and invalid outputs?
 - Temporal or Spatial Multiple Bit-Upset (MBU) should generate (with high probability) a diagnosable error



7



Related Work: Impact on Commercial Systems



- Variable Strength ECCs have been employed for reliable cache operation under aggressive voltage scaling [8]
- For processor caches operating at NTV, TMR is employed as a low-complexity means for improved resilience as compared to ECC schemes [9]
- Employing Modular Redundancy for High-Performance Computing (HPC) systems can significantly increase compute node *availability* [C. Engelmann et al. 2009]
 - HPC systems: decreasing MTTF, increasing MTTR due to scaling
 - Checkpoint and Restart is too costly (for complex HPC applications, increasing volume of state information needs to be saved)
 - Employing compute-node (processor(s), memory module(s), network interface) level redundancy permits to tradeoff individual component reliability by a factor of 100-100,000 → \$ Less Expensive \$

8



Limitations of NTC: Process Variations



- Near-Threshold Computing provides *Energy-Efficiency*
 - >10X Performance Loss → Parallelization [11], Device optimization [1]
 - (add-on) 5X Impact of Performance Variation → *Cost of Design Margins?*
- Nanoscale CMOS devices have Performance variability caused due to manufacturing-induced Process Variations (PV) [12].
 - For example, Random Dopant Fluctuations (RDF) are due to implanted impurity fluctuation and cause local variation (intra-die) in the threshold voltage of the transistors → *Increase in Delay Margins*
 - Impact of Technology Scaling: RDF magnified as number of dopant atoms is fewer so addition or deletion of just a few impurity atoms significantly alters transistor properties
- Operation near the threshold voltage of the transistors further exacerbates the process variability [1],[13]



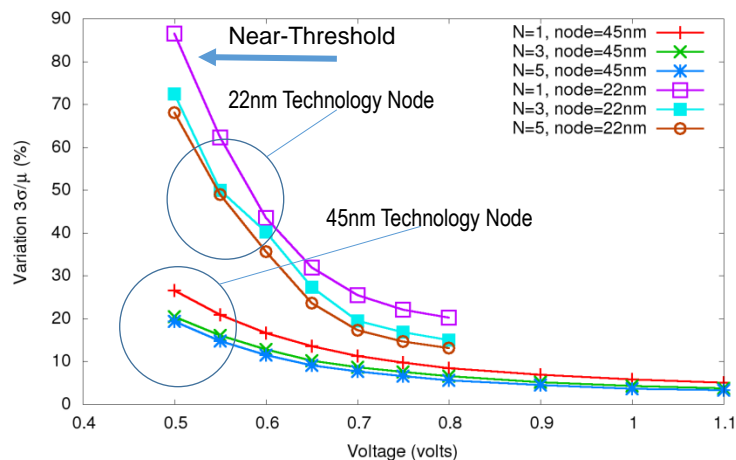
Source: Borkar, Intel



Limitations of NTC: Delay Variations



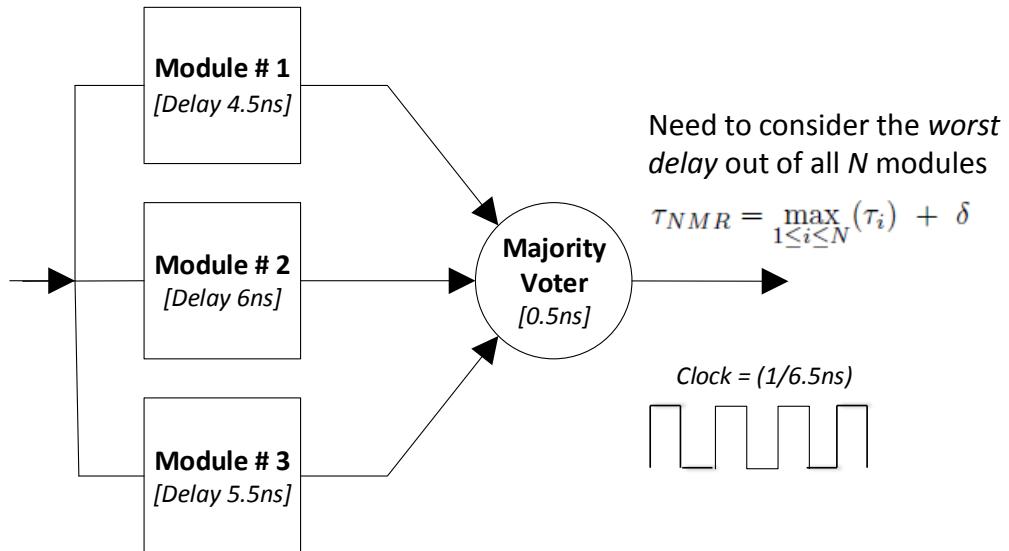
- Delay measurements of FO4 Inverter Chains
- Implemented using PTM cards



10



Modular Redundancy at NTV: What is the catch?



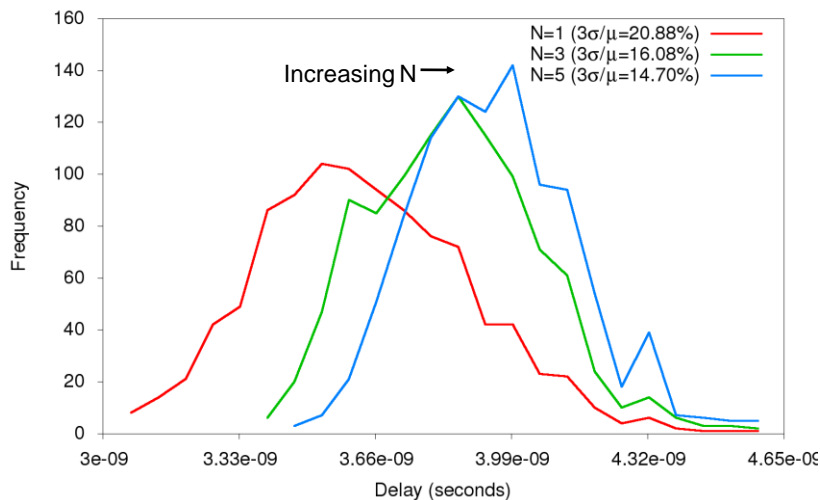
11



N-MR system Delay Distributions under PV



Delay Distributions (1000 arrangements each) at NTV of 0.55V
with 45nm PTM model cards



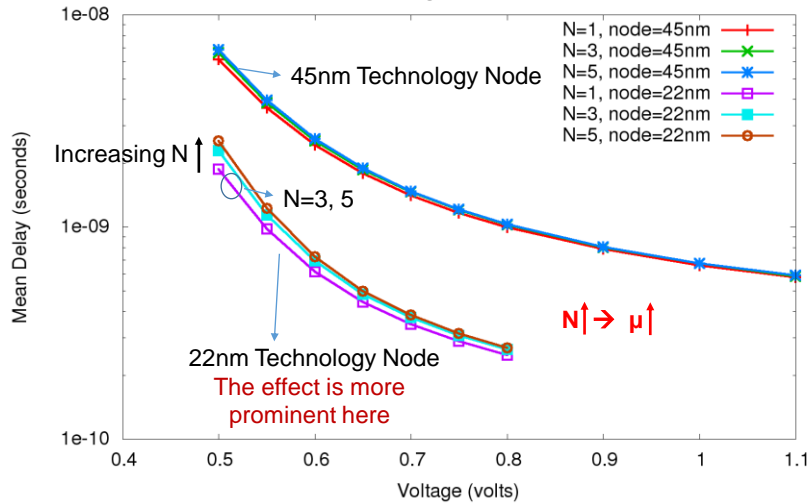
12



Performance of N -MR systems with scaled technology nodes



Mean delay difference of N -MR systems increases with voltage scaling down to Near-threshold region



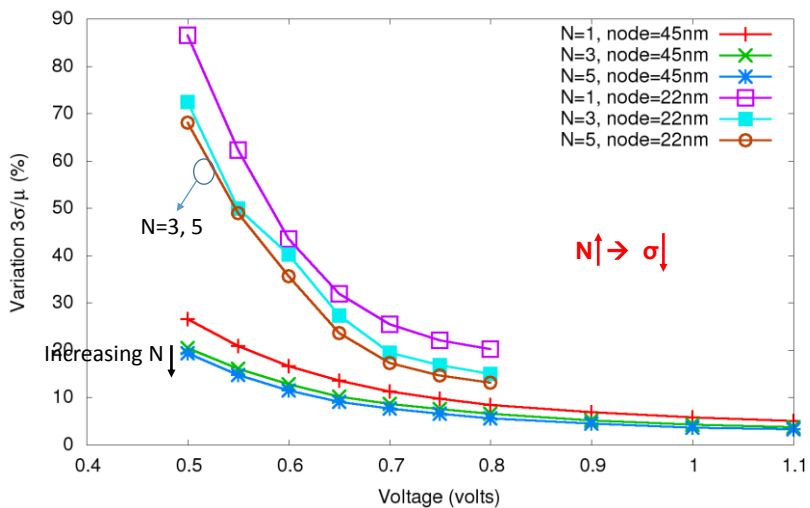
13



Performance of N -MR systems and variability



Delay Variations decrease with increasing N for N -MR systems



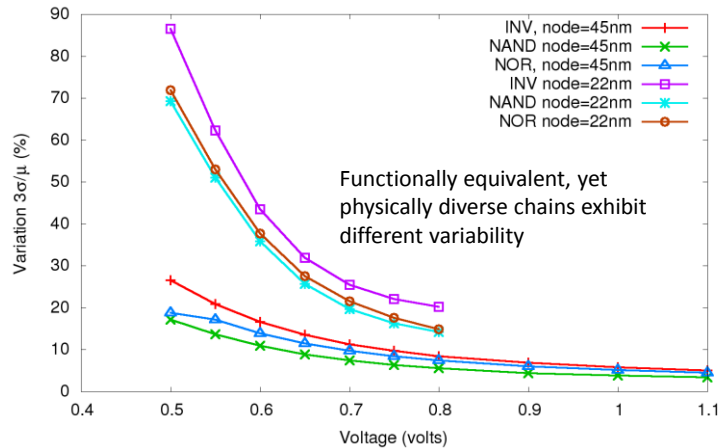
14



Reducing variability at NTV



- Variability is dependent on length of the critical path. More gates imply less variability [14]
- Type of logic gate utilized can impact variability



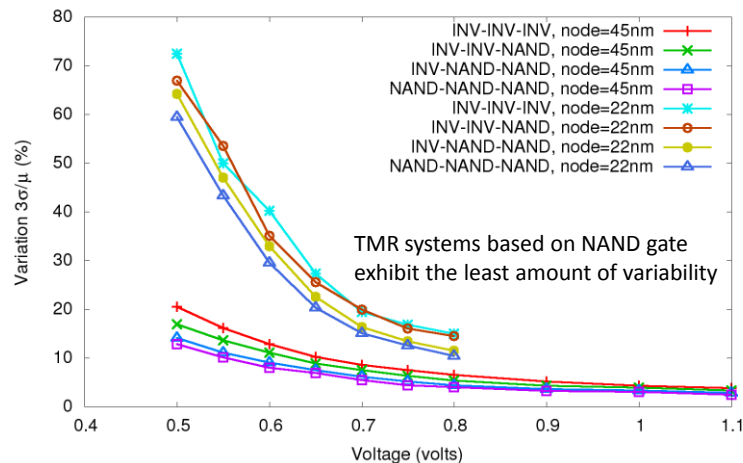
15



Reducing variability at NTV



- Develop a synthesis technique which realizes same function utilizing different gates with the goal of minimizing variability within given constraints



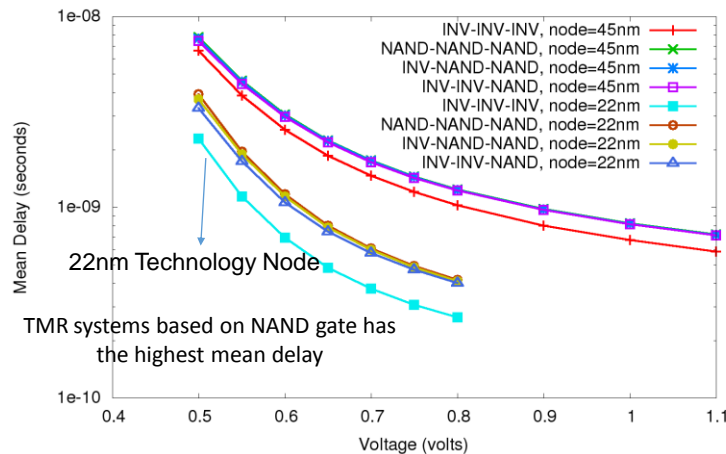
16



Future work: synthesizing variability immune circuit for NTV operation



- For our experiments with the inverter chains, the mean delays for NAND-based systems are higher than INV-based systems which outweighs any benefit of reduced variation.



17



Energy Cost of Mitigating Variability



- “One-Time” Timing Guard-bands
 - Voltage and/or Frequency Margin [15]
- For a fixed V_{DD} of simplex system, how much voltage margin (ΔV_{DD}) needs to be added for N -MR system?
 - Left-shift the distribution of NMR system towards that of the simplex system
- Condition for same 99% Yield for N -MR system as compared to simplex system i.e., same delay [14]
 - (for $N \geq 3$): $\mu_{N-MR} + 3\sigma_{N-MR} \leq \mu_{Simplex} + 3\sigma_{Simplex}$
- How much energy overhead for N -MR system?
 - N -fold as mostly assumed with N -MR systems

18



Experimental Setup



- MCNC benchmark circuits c880, i5
- 45nm-based NanGate open source library [16]
- Synopsys Design Compiler used for synthesis
- Worst-case Test Vectors are generated using Synopsys TetraMax
- Synthesized netlists are imported into HSPICE for Monte-Carlo simulations
- Voter delay is not considered to make direct comparison to simplex systems



Goddard Cartoon ©PharmaVentures, all rights reserved

http://images.dailytech.com/nimage/22944_large_2007_08_monte_carlo.jpg

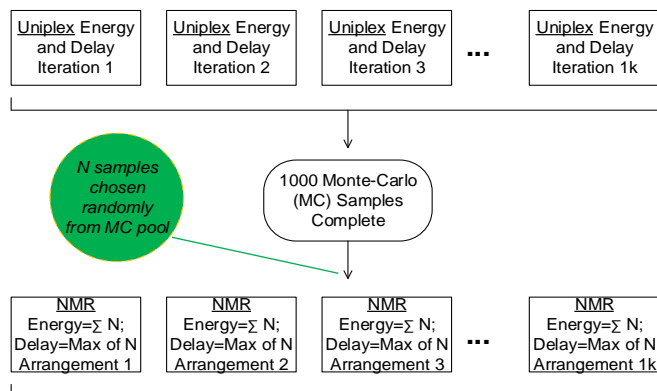
19



Experimental Setup



- At least 1000 Monte-Carlo iterations are performed
- μV_{th} from Predictive Technology Model (PTM) cards
- RDF: σV_{th} ranges from 25.9mV (45nm) to 59.9mV (22nm) [12]



20

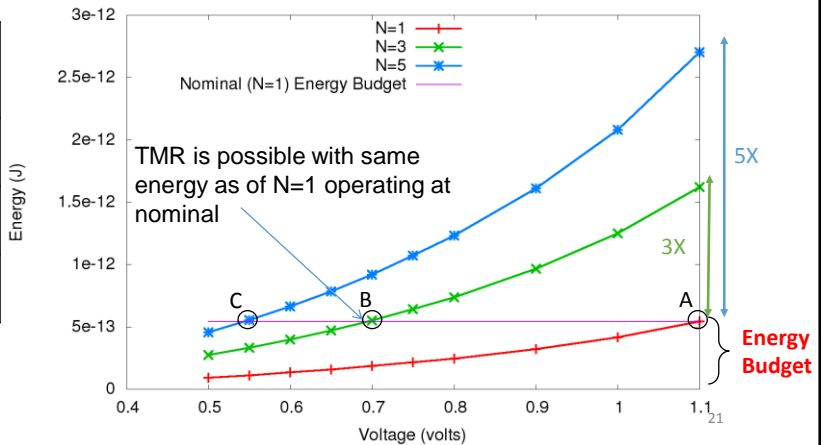


Results: Energy-Efficiency vs Reliability



- Energy measurements of FO4 Inverter Chains implemented using 45nm PTM cards

Operating Point	V_{DD} (V)	Normalized Energy	Normalized Delay
A	1.1	1X	1X
B	0.69	~1X	2.58X
C	0.545	~1.01X	7.15X



Energy Consumption of N -MR systems



- How much Voltage Margin (VM) expressed as ΔV_{DD} needs to be included for N -MR system?
- Even though N -MR systems exhibit higher mean delays, the reduced variance necessitates only a slight VM to meet the delay target of the simplex system
- On average 2mV increase in V_{DD} is satisfactory to operate a TMR arrangement based on $i5$ circuit at comparable delay

Benchmark \rightarrow	c880		i5	
Simplex, V_{DD} (NTV)	N=3	N=5	N=3	N=5
0.55 V	3.03X \uparrow	5.06X	3.02X	5.05X
0.6 V	3.03X	5.05X	3.02X	5.04X
0.65 V	3.02X	5.04X	3.02X	5.04X
0.7 V	3.01X	5.03X	3.01X	5.02X



Results of VM: Increased Variability



- The mean delays for the 22nm (45nm) node with $N = 3$ & $N = 5$ are 1.16X (1.06X) and 1.24X (1.09X) the mean delay for a simplex system respectively at the same voltage of 0.55V
- The 22nm node-based 5MR system requires 3.94% more energy consumption than a similar configuration at 45nm
- At NTV of 0.5V for simplex arrangement, a 11mV increase in V_{DD} is required for the TMR arrangement for same performance

Technology Node →	45nm		22nm	
	N=3	N=5	N=3	N=5
simplex, V_{DD} (NTV)				
0.5 V	3.04X	5.07X	3.17X	5.30X ↑
0.55 V	3.03X	5.05X	3.14X	5.27X
0.6 V	3.03X	5.04X	3.13X	5.26X
0.65 V	3.02X	5.03X	3.12X	5.23X
0.7 V	3.01X	5.02X	3.10X	5.16X



Conclusions and Future Work



- Redundancy provides a degree of freedom for increased reliability by diminishing the supply voltage
- Feasible when resulting increase in delay is tolerable
- Further study worthwhile to determine resilience provided by N -MR systems at NTV due to other noise sources such as:
 - Variation in supply voltage V_{DD} and Temperature
 - Expect a further variation of 2X [1] (*detrimental effect anticipated*)
 - Aging-induced variations [13]
 - Lower Voltage and Junction temperatures will lower aging effects such as Bias-Temperature Instability (*beneficial effect anticipated*)
 - Lower temperature and currents help to reduce interconnect defects due to Electromigration (*beneficial effect anticipated*)



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25



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26